

Notice of References Cited	Application/Control No. 10/576,405	Applicant(s)/Patent Under Reexamination HADA ET AL.	
	Examiner Anca Eoff	Art Unit 1795	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2007/0065748	03-2007	Hada et al.	430/270.1
*	B	US-2002/0132181	09-2002	Nishimura et al.	430/270.1
*	C	US-2005/0095532	05-2005	Kodama et al.	430/270.1
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	K	US-			
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	M	US-			

FOREIGN PATENT DOCUMENTS

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	N					
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NON-PATENT DOCUMENTS

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	U	Padmanaban M., Dammel R., Lee S., Kim W., Kudo T., McKenzie D., Rahman D. - "Performance of Imide and Methide Onium PAGs in 193 nm Resist Formulations", Advances in Resist Technology and Processing XX, Proceedings of SPIE Vol. 5039 (2003), pages 743-751
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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